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Attorney's Docket No. 5308-157IP2

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Das et al.

Confirmation No.: 3570

Serial No.: 10/045,542

Group Art Unit: 1762

Filed: October 26, 2001

For: METHOD OF FABRICATING AN OXIDE LAYER ON A SILICON CARBIDE  
LAYER UTILIZING AN ANNEAL IN A HYDROGEN ENVIRONMENT

Date: October 21, 2002

Commissioner for Patents  
Washington, DC 20231


**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Sir:

Attached is a form PTO-1449, together with a copy of the identified document(s).  
This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(b),  
within three months of the filing date of the above-referenced application or before the  
mailing of a first Office Action on the merits, whichever event occurs last. Accordingly, no  
fee is required.

The Commissioner is hereby authorized to charge any additional fee that may be  
required or credit any refund to our Deposit Account No. 50-0220.

Respectfully submitted,

  
Timothy J. O'Sullivan  
Registration No. 35,632

**Customer Number:**



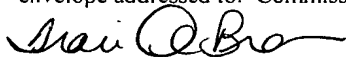
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PATENT TRADEMARK OFFICE

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**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an  
envelope addressed to: Commissioner for Patents, Washington, DC 20231 on October 21, 2002.



Traci A. Brown

Date of Signature: October 21, 2002